

**IN THE UNITED STATES
PATENT AND TRADEMARK OFFICE**

Appl. No. : 10/765,647
Applicant(s): Laura Wills Mirkarimi
Filed: January 26, 2004
TC/A.U.: 1700/1765
Examiner: Duy Vy Nguyen Deo
Atty. Docket: 10030753-01
Confirmation No.: 1183
Title: Method for Etching High Aspect Ratio
Features in III-V Based Compounds for
Opto Electronic Devices

**AMENDMENT and/or RESPONSE ACCOMPANY REQUEST FOR CONTINUED
EXAMINATION under 37 C.F.R. § 1.114**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In conjunction with the RCE filed herewith, please amend the above referenced application as follows and reconsider the application in light of the following remarks.

This paper includes (each beginning on a separate sheet):

1. Remarks/Discussion of Issues;